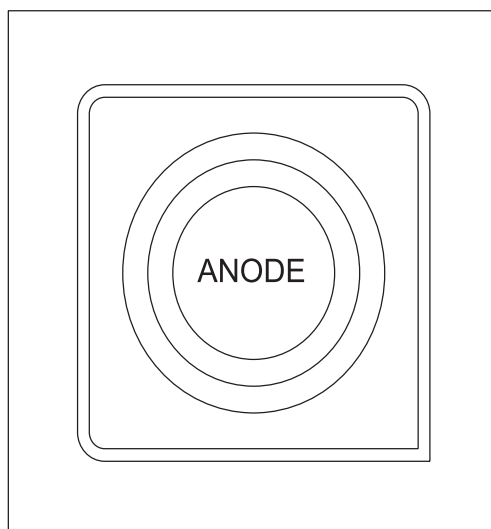


PROCESS DETAILS

Process	EPITAXIAL PLANAR
Die Size	9.0 x 9.0 MILS
Die Thickness	7.1 MILS
Anode Bonding Pad Area	4.8 MILS DIAMETER
Top Side Metalization	Al - 30,000Å
Back Side Metalization	Au - 12,000Å

GEOMETRY



BACKSIDE CATHODE

R0

GROSS DIE PER 4 INCH WAFER

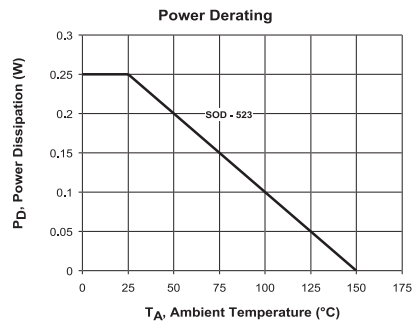
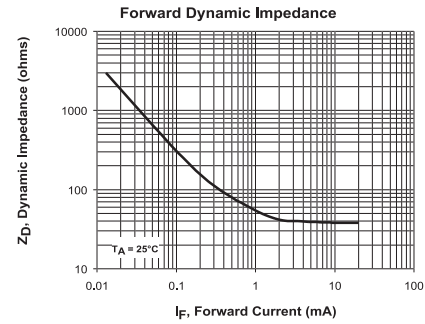
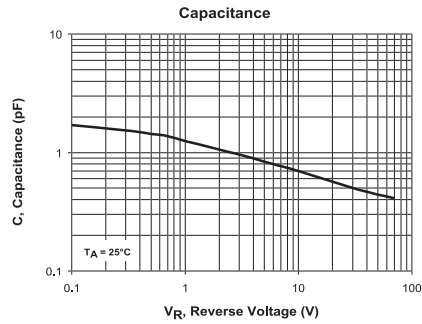
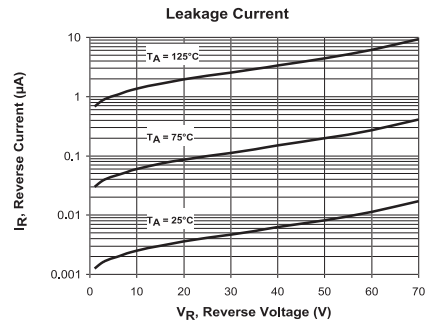
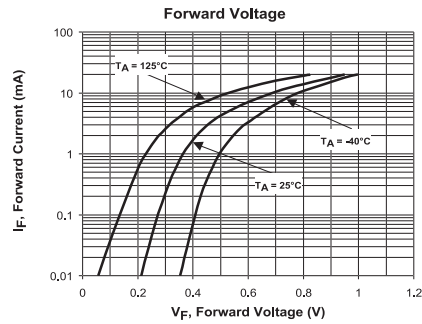
139,050

PRINCIPAL DEVICE TYPES

CMDD6263
CMKD6263
CMLD6263 Series
CMOD6263
CMPD6263 SERIES
CMSD6263 SERIES
CMUD6263 Series
1N6263

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